

ABSTRACT

The present invention provides a method for polishing a glass substrate by which the polishing speed in polishing processing for polishing a surface of a glass substrate using cerium oxide as polishing abrasive particles can be increased.

The method for polishing a glass substrate according to the present invention is a method in which a polishing liquid containing cerium oxide as polishing abrasive particles is supplied to a surface of the glass substrate that is to be polished, and the surface of the glass substrate is subjected to the polishing processing. Here,

an alkaline polishing liquid that contains the above-described cerium oxide as polishing abrasive particles and further contains an inorganic reducing agent is used as the above-described polishing liquid.